

# Photoresist Strip

## For Microposit 1813 POSITIVE Photoresist

## User Guide

This *User Guide* provides a standard procedure for stripping photoresist from a silicon wafer.

**Note:** Always manipulate wafers with clean tweezers. Teflon-coated tweezers recommended (for cleanliness) if available.

### Preparation

**Note:** Always prepare chemicals in a ventilated hood (wet bench)

1. Fill about 1 cm of acetone in container large enough to hold wafer. Affix **acetone** label if necessary

2. Fill about 1 cm of methanol in container large enough to hold wafer. Affix **methanol** label if necessary.



Labeled acetone container



Labeled methanol container

### Cleaning Procedure

1. Place wafer, face up, in acetone. Soak for 2 minutes.

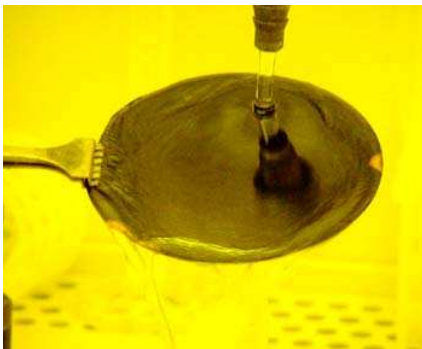
**Tip:** Jostle the wafer and/or container slightly to help remove the photoresist, taking care not to spill.

2. Transfer wafer to methanol. Soak for 2 minutes.

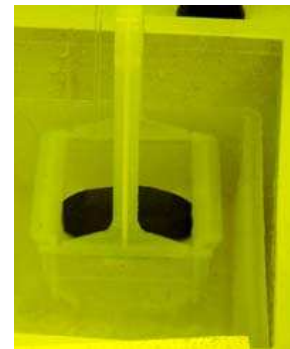
**Tip:** Jostle the wafer and/or container slightly to help clean the wafer, taking care not to spill.

3. Rinse wafer with DI-H<sub>2</sub>O.

**Tip:** First rinse the wafer under a stream of DI-H<sub>2</sub>O, being careful not to drop the wafer. Then place it in a submerged wafer carrier for 1 minute.



Rinse under running DI H<sub>2</sub>O stream



Rinse in wafer carrier  
(with running water)

4. Dry wafer with nitrogen.

**Tip:** The best drying method: automated nitrogen wafer dryer (see *UserMan-N2Dryer* manual).

**Tip:** A pressurized nitrogen nozzle may be the most readily available for wafer drying. However, be sure to have a strong grip on the wafer (with tweezers)!! Be sure to dry BOTH sides of the wafer.